



Substitute for form 1449B/PTO			<b>Complete if Known</b>		
			Application Number	TO BE ASSIGNED (DIV1)	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)			Filing Date	March 8, 2002	
			First Named Inventor	Bruce W. Smith	
			Group Art Unit	2851	
			Examiner Name	Hung NGUYEN	
			Attorney Docket Number	81468.284420	
Sheet	2	of	2		

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
HW	15	S. Asai, et al., "High Performance Optical Lithography Using a Separated Light Source", <u>J. Vac. Sci. Technology</u> , Vol B 10(6), pp. 3023-3026, (November/December 1992).	
	16	E. Tamechika, et al., "Investigation of Single Sideband Optical Lithography Using Oblique Incidence Illumination", <u>J. Vac. Sci. Technology</u> , Vol. B 10(6), pp. 3027-3031, (November/December 1992).	
	17	W.N. Partlow, et al., "Depth of Focus and Resolution Enhancement for i-line and Deep-UV Lithography Using Annular Illumination", <u>SPIE Optical/Laser Microlithography</u> , Vol. 1927, pp. 137-156, (1993).	
	18	T. Ogawa, et al., "The Effective Light Source Optimization With the Modified Beam For the Depth-of-Focus Enhancements", <u>SPIE Optical Laser Microlithography</u> , Vol. 2197, pp. 19-30, (1994).	
	19	T. Ogawa, et al., "Sub-Quarter Micron Optical Lithography With Practical Super Resolution Technique", <u>SPIE Optical Laser Microlithography VIII</u> , Vol. 2440, pp. 772-783, (1995).	
	20	B. W. Smith, et al., "Illumination Pupil Filtering Using Modified Quadrupole Apertures", <u>SPIE Optical Microlithography XI</u> , Vol. 3334, pp. 37-47, (1998).	
	21	B.W. Smith, et al., "Influences of Off-Axis Illumination on Optical Lens Aberration", <u>J. Vac. Sci. Technology</u> , Vol. B16(6) 3398, pp. 3405-3410, (November/December 1998).	
	22	Chin C. Hsia, et al., "Customized Off-Axis Illumination Aperture Filtering for Sub 0.18 um KrF Lithography", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 39-46, (1999).	
	23	P. Zandbergen, et al., "Optical Extension at the 193nm Wavelength", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 29-38, (1999).	
	24	Z. Yang, et al., "Corrections of Aberrations Using HOE's in UV and Visible Imaging Systems", <u>SPIE International Lens Design Conference</u> , Vol. 1354, pp. 323-327, (1990).	
HW	25	B. W. Smith, <u>Microlithography: Science and Technology</u> , Chapter 3, New York: Marcel Dekker (1998), pp. 216-231.	

Examiner Signature	H. Nguyen	Date Considered	6/19/03
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Unique citation designation number. <sup>2</sup> Applicant is to place a check mark here if English language Translation is attached.

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